



Call for Papers – DPS 2018

40th International Symposium on Dry Process

November 13(Tue) – 15(Thu), 2018

Nagoya University, Nagoya, Aichi, Japan



Fried Chicken Wing



Paper Submission Deadline: July 13, 2018

Author instructions and information about DPS can be found at:

<http://www.dry-process.org/2018/>

40th Anniversary International Symposium on Dry Process (DPS2018) will be held at Nagoya University, Nagoya, Aichi, in Japan, from November 13 to 15, 2018. The Symposium covers all aspects of the rapidly evolving fields of dry processes, including but not limited to plasma etching and deposition processes, diagnostics and modeling of plasmas and surfaces, and surface modifications by plasmas, for the applications in, e.g., microelectronics, power devices, sensors, environmental protection, biological systems, and medicine. The DPS has provided valuable forums for in-depth discussion among professionals and students working in this exciting field for more than three decades.

Theme: Dry processes and related technologies from fundamentals to applications

Topics: 1. Etching Technologies

2. Manufacturing Technologies (AEC, APC, EES, FDC)
3. Surface Reaction and Damage
4. Plasma Diagnostics and Monitoring Systems
5. Modeling and Simulation
6. Plasma Generation (Equipment/Source)
7. Deposition Technologies (CVD / PVD)
8. Atomic Layer Processes (ALD/ALE)
9. Plasma Processes for 3D Device, FPD, Photovoltaic Devices
10. Plasma Processes for New Material Devices (MRAM, Power, Organic)
11. Plasma Processes for Biological and Medical application, MEMS
12. Atmospheric Pressure Plasma and Liquid Plasma
13. New Dry Process Concepts

Arranged session:

- A1. Control of surface reactions in atomic-precision plasma processing (ALE/ALD)
- A2. Etching challenges in extremely high-aspect-ratio (HAR) features (AR > 100)

For further general information, please contact: **e-mail: dps2018@officepolaris.co.jp**

Organizing Committee Chair: Keizo Kinoshita (AIO Core Co., Ltd.)

Executive Committee Chair: Masaru Hori (Nagoya University)

Program Committee Chair: Masanaga Fukasawa (Sony Semiconductor Solutions Corp.)

Publication Committee Chair: Tatsuo Ishijima (Kanazawa University)

Ad Hoc Committee Chair for 40th Anniversary Project: Kenji Ishikawa (Nagoya University)

URL: <http://www.dry-process.org/2018/>